

Application No. 09/756,140  
Art Unit 1755  
February 18, 2004  
Reply to Office Action of August 26, 2003

**AMENDMENTS TO THE CLAIMS**

This listing of claims will replace all prior versions, and listings, of claims in the present application.

**Listing of Claims:**

1. **(Currently Amended)** An abrasive for metal comprising an oxidizing agent, water and a polymer particle having a functional group that traps a metal ion, wherein the functional group that traps a metal ion is at least one selected from the group consisting of ~~OH, COOM, >C=O, O, COOR, CONH<sub>2</sub>, NO, NO<sub>2</sub>, >N-O, SO<sub>3</sub>M, PHO(OM), PO(OM)<sub>2</sub>, AsO(OM)<sub>2</sub>, N=N, >C=N, >C=N-OH, >C=NH, SCN, SH, S, >C=S, COSM, CSSM, CSNH<sub>2</sub>, NCS, >P, >As, SeH, >S-Se, CSeSeM, amino alcohol, aminophosphonic acid and iminodiacetic acid, wherein M represents a hydrogen, an alkali metal, an alkaline earth metal or an ammonium group and R represents a hydrocarbon.~~ acid.

2-3. **(Canceled)**

4. **(Original)** The abrasive for metal according to claim 1, wherein the particle having a functional group is a particle comprising an ion exchange resin.

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5. **(Previously Presented)** The abrasive for metal according to claim 1, wherein the particle having a functional group that traps a metal ion is a particle comprising an ion exchange resin, and the average particle diameter of the particle is 1.0  $\mu\text{m}$  or less.

6. **(Original)** The abrasive for metal according to claim 1, wherein the particle having a functional group is a particle comprising a chelate resin.

7. **(Original)** The abrasive for metal according to claim 1, wherein the particle having a functional group is a particle comprising a chelate resin, and the average particle diameter of the particle is 1.0  $\mu\text{m}$  or less.

8. **(Original)** A process for producing the abrasive for metal according to claim 5, wherein the process comprises wet-milling an ion exchange resin.

9. **(Previously Presented)** A process for producing the abrasive for metal according to claim 5, wherein the process comprises dry-milling and then wet-milling an ion exchange resin.

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10. (**Original**) The process for producing the abrasive for metal according to claim 7, wherein the process comprises wet-milling chelate resin.

11. (**Previously Presented**) The abrasive for metal according to claim 1, wherein the metal is copper or copper alloy.

12. (**Original**) A polishing composition for metal comprising an abrasive for metal according to claim 1, an oxidizing agent and water.

13. (**Previously Presented**) The polishing composition for metal according to claim 12, wherein the metal is copper or copper alloy.

14. (**Original**) The polishing composition for metal according to claim 12, wherein the oxidizing agent is hydrogen peroxide.

15. (**Original**) The polishing composition for metal according to claim 12, wherein the composition further comprises at least one selected from the group consisting of a spherical particle, benzotriazole and a benzotriazole derivative.

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16. (**Original**) A process for polishing a metal by chemical mechanical polishing, wherein the process is conducted by using the polishing composition for metal according to claim 12.

17. (**Previously Presented**) The process according to claim 16, wherein the metal is copper or copper alloy.

18. (**Previously Presented**) The abrasive for metal according to claim 1, wherein said particle having a functional group is a particle comprising a cation exchange resin.

19. (**Previously Presented**) The abrasive for metal according to claim 1, wherein said particle having a functional group is a particle comprising an anion exchange resin.